

Conference Proceedings

This issue of the *Journal of Applied Crystallography* contains the written versions of most of the invited and many of the contributed papers presented at the 8th International Conference on Small-Angle Scattering, held at Leuven, Belgium, 6–9 August 1990. The Co-editorial work for this issue was almost entirely (except for his own paper) entrusted to Gernot Kostorz, ETH Zürich, who served as a Co-editor of this journal from 1980 to 1989. This ensured that the usual thorough publication standards were maintained in the interest of all authors and readers.

This is the largest number of review and research papers in the field of small-angle scattering ever assembled in one collection. I consider that the broad coverage of the field and the individual quality of each contribution will serve as a valuable source of reference to specialists and beginners alike for several years to come.

A. M. GLAZER

Editor, *Journal of Applied Crystallography*

Eighth International Conference on Small-Angle Scattering Leuven, Belgium, 6–9 August 1990

The eighth conference was held at the University of Leuven with the purpose of providing an international forum where scientists applying small-angle scattering in various fields and those working on methodology could meet. 206 participants from 26 countries attended the conference.

The Local Organizing Committee consisted of G. Groenickx, J. Helsen, G. S. D. King, R. Mewis, H. Reynaers and L. van Tichelen.

An International Advisory Board was consulted to shape the main topics of the conference. The members of this board were: J. Baldrian (Prague), H. Benoit (Strasbourg), J. Bordas (Daresbury), H. Brumberger (Syracuse), A. Craievich (Campinas), G. Damaschun (Berlin), L. Feigin (Moscow), V. Gerold (Stuttgart), A. Guinier (Paris), Y. Hiragi (Kyoto), J. Kjems (Risø), G. Kostorz (Zurich), O. Kratky (Graz), V. Luzzati (Gif-sur-Yvette), P. Moore (New Haven), W. Ruland (Marburg), P. W. Schmidt (Columbia).

The Programme Committee, F. Fontaine (Liège), M. Koch (Hamburg), A. Naudon (Poitiers), J. Point (Mons), C. van Dijk (Petten), C. G. Vonk (Geleen), A. Vrij (Utrecht), G. S. D. King (Leuven) and H. Reynaers (Leuven), produced a programme of 6 plenary papers, 19 invited papers and 127 contributed papers of which 31 were presented orally during parallel sessions and 96 during two poster sessions. Inspection of the total set of contributions makes clear that small-angle scattering of X-rays and neutrons continues to grow in a strongly interdisciplinary way with special emphasis on materials science.

During the closing ceremony it was agreed to entrust the organization of the Ninth International Conference to J. P. Cotton and J. Teixeira of the Laboratoire Léon Brillouin. This will be organized at Saclay in 1993.

The conference was generously supported by the National Science Foundation of Belgium (NFWO), the University of Leuven and industrial sponsorship from DSM (Geleen), Philips-MBLE (Brussels), Dow Chemical (Terneuzen), Exxon Chemical International (Brussels), Siemens (Brussels), Solvay (Brussels), Maes (Waarloos), ICI (Everberg), Raychem (Kessel-lo), Kaneka (Oevel), Agfa-Gevaert (Mortsel), Rigaku Europe (Dusseldorf) and Bank Brussel-Lambert.

The manuscripts of the papers contained in this issue were submitted during or after the conference. They were all evaluated by at least two referees and all accepted papers were improved in this process. The first paper was ready for technical editing on 3 October 1990; the last one (which was not the last one submitted!) on 16 April 1991. Thanks to the efforts of 109 referees, many of them working on several manuscripts, and the prompt response of (most) authors, it was thus possible to maintain the originally planned production schedule and date of publication.

The International Union of Crystallography kindly agreed to publish these conference papers in the *Journal of Applied Crystallography*. Special thanks are due to Michel Schlenker, Editor of *Journal of Applied Crystallography* until 1990, for his kind and efficient help during the preparation of the editorial matters, to Mike Glazer, the present Editor, and to Mike Dacombe, the Technical Editor, and his editorial staff at Chester for the extra effort necessary to accomplish this now completed issue.

HARRY REYNAERS
Conference Chairman
Leuven, Belgium

GERNOT KOSTORZ
Guest Editor
Zürich, Switzerland